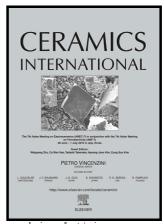
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ACCEPTED MANUSCRIPT

Influence of growth temperature on the microstructure and electrical transport $properties\ of\ epitaxial\ NiCo_2O_4\ thin\ films$

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Abstract

In the work reported here, $NiCo_2O_4$ films were grown epitaxially on LaAlO₃ (111) substrates at temperatures between room temperature and 700 °C. The effects of the substrate temperature (T_{sub}) on the structural, electrical and magnetic properties and on the Hall effect of the film were investigated. T_{sub} has a great influence on the cation disorder. High T_{sub} makes substitution of Ni (Oh) for Co (Td) easier, and changes the relative Ni^{3+}/Co^{3+} concentration. The film grown at 400 °C had a

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